

FIS920000409US1

I26-0013

CLEAN VERSION OF AMENDMENTS**IN THE CLAIMS**

Please amend Claim 5 as follows in re-written "clean" format:

A1 5. (Amended/Clean) The process according to Claim 4, wherein the focused ion beam current comprises an energy from about 500 to 3,000 picoAmps.

[Please add Claim 13 as follows:]

A2 13. (Newly added) The process according to Claim 1, wherein absorbing the halogen gas comprises forming at least a saturated monolayer of the halogen gas onto the surface.